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## PATENT WITHDRAWAL NOTICE

DATE WITHDRAWN

7/16/07

15625

The following application has been WITHDRAWN from the

Tuesday, July 24, 2007 issue.

SERIAL NO.

PATENT NUMBER

10/706,902

7,247,253

DRAWINGS

CLASS

0

216/066

TITLE

SELECTIVE ETCH PROCESS OF A SACRIFICIAL LIGHT ABSORBING MATERIAL (SLAM) OVER A DIELECTRIC MATERIAL

NAME AND ADDRESS

HEE YEOP CHAE, ET AL SAN JOSE, CA

REASON FOR WITHDRAWAL

Office of Petitions granted applicant's request to withdraw patent from issue.

APPROVED

/ Mary Louise McAskill, Manager /

Statistical Analysis Division

FORM PTO-302 -- (REV. 04-2007)